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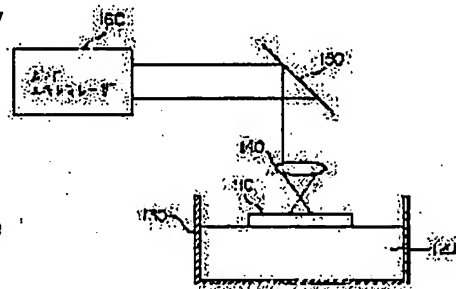
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(54) METHOD AND APPARATUS FOR MODIFICATION OF SURFACE OF FLUORORESIN

(57)Abstract:

PURPOSE: To enable an extensive surface modification of a fluoro-resin by bringing the fluoro-resin into contact with an aq. soln. of a specific compd. and irradiating the contact surface of the fluoro-resin with UV radiation to render the surface hydrophilic.

CONSTITUTION: An aq. soln. 120 of a water-soluble compd. having a C-H bond or an N-H bond is put in a vessel 130. A fluoro-resin 110 is floated on the aq. soln. 120. The contact surface of the fluoro-resin 110 with the aq. soln. 120 is irradiated with UV radiation from a radiation source 160 via a total reflection mirror 150 and a lens 140 to render the contact surface of the fluoro-resin 110 hydrophilic.



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